

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Seok-Yoon YANG, et al.)	
Serial No.:	10/675,455)	Group Art Unit: 1795
)	
Filed:	September 30, 2003)	Examiner:
)	Walke, Amanda C.
For:	PHOTOSENSITIVE RESIN COMPOSITION)	
	CONTROLLING SOLUBILITY AND PATTERN)	Confirmation No. 5598
	FORMATION METHOD OF DOUBLE-LAYER)	
	STRUCTURE USING THE SAME)	

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

**RESPONSE TO FINAL OFFICE ACTION
UNDER 37 CFR § 1.116, WITH AMENDMENT**

Dear Sir:

In response to the Final Office action mailed on July 10, 2008, Applicants request reconsideration in view of the following remarks for entry in the above-identified application. This reply is being submitted with a Petition of one-month extension of time. Please charge an appropriate extension fee to Deposit Account No. 06-1130.

Listing of the Claims currently on file begins on page 2 of this paper; and
Remarks begin on page 6 of this paper.

Attachments: Certified English translation for Korean Patent Application No. 10-2002-0060500 filed on October 4, 2002.